



1744

PATENT
Attorney Docket No.: SSI-08200

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	Group Art Unit: 1744
William Dale Jones)	Examiner:
Serial No.: 10/630,640)	<u>TRANSMITTAL LETTER</u>
Filed: July 29, 2003)	162 N. Wolfe Road
For: REGULATION OF FLOW OF)	Sunnyvale, CA 94086
PROCESSING CHEMISTRY ONLY)	(408) 530-9700
INTO A PROCESSING CHAMBER)	Customer No.: 28960

Commissioner for Patents
P.O. Box 1450
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Sir:

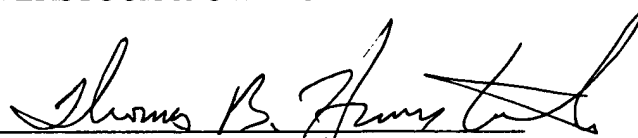
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The Commissioner is hereby authorized to charge any additional fee or credit overpayment to our Deposit Account No. 08-1275. **An originally executed duplicate of this transmittal is enclosed for this purpose.**

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 1-14-04

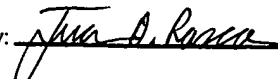
By: 
Thomas B. Haverstock
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CERTIFICATE OF MAILING (37 CFR § 1.8(a))

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Date: 1-14-04 By: 



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Serial No.: 10/630,640

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For: **REGULATION OF FLOW OF
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) Group Art Unit: 1744

) Examiner:

) **INFORMATION DISCLOSURE
STATEMENT**

) 162 N. Wolfe Road
) Sunnyvale, CA 94086
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Alexandria, VA 22313

Sir:

The citations listed below, copies attached, may be material to the examination of the above-identified application, and are therefore submitted in compliance with the duty of disclosure defined in 37 C.F.R. §§ 1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

United States Patents or Published Patent Applications have been filed electronically (EFS ID #53516); (EFS ID #53518); (EFS ID #53520); (EFS ID #53521); (EFS ID #53522); (EFS ID #53523); and (EFS ID #53526). Applicants have become aware of the following printed publication which may be material to the examination of this application:

- Chinese Publication No. CN 1399790 A;
- German Publication No. DE 36 08 783 A1;
- German Publication No. DE 39 04 514 C2;
- German Publication No. DE 39 06 724 C2;
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- German Publication No. DE 39 06 737 A1;
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- Japanese Patent Abstract JP 2-209729;
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- PCT Publication No. WO 90/13675;
- PCT Publication No. WO 91/12629;
- PCT Publication No. WO 93/14255;
- PCT Publication No. WO 93/14259;
- PCT Publication No. WO 93/20116;
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This Information Disclosure Statement under 37 C.F.R. §§ 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that anyone or more of these citations constitutes prior art.

Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 1-14-04

By: Thomas B. Haverstock
Thomas B. Haverstock
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Attorneys for Applicant

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT
(Use Several Sheets If Necessary)

Applicant: William Dale Jones

Filing Date: July 29, 2003

Group Art Unit: 1744

(37 CFR § 1.925)

FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS

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						Yes	No
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FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS

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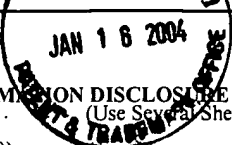
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FORM PTO-1449 (Modified)		U.S. Department of Commerce Patent and Trademark Office		Attorney Docket No.: SSI-08200		Serial No.: 10/630,640		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)				Applicant: William Dale Jones				
(37 CFR § 1.98(h))				Filing Date: July 29, 2003		Group Art Unit: 1744		
FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS								
		Document Number	Publication Date	Country / Patent Office	Class	Subclass	Translation	
							Yes	No
	CS	WO 01/78911 A1	10/25/01	PCT	B08B	3/00		X
	CT	WO 01/85391 A2	11/15/01	PCT	B24B			X
	CU	WO 01/94782 A3	12/13/01	PCT	F04B	43/02		X
	CV	WO 02/09894 A2	02/07/02	PCT	B08B			X
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OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication)					
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	EC	Gabor, A. et al., "Block and Random Copolymer resists Designed for 193 nm Lithography and Environmentally Friendly Supercritical CO ₂ Development," SPIE, Vol. 2724, pp. 410-417, Jun. 1996.			
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(Modified)U.S. Department of Commerce
Patent and Trademark Office

Attorney Docket No.: SSI-08200

Serial No.: 10/630,640

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(Use Several Sheets If Necessary)

Applicant: William Dale Jones

(37 CFR § 1.98(b))

Filing Date: July 29, 2003

Group Art Unit: 1744

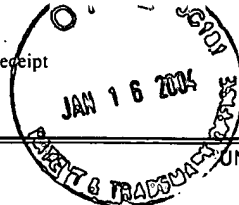
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Electronic Version 1.1

Stylesheet Version v1.1.1

Title of Invention	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER										
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EFS ID:	53516										
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Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
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Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney					

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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

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Stylesheet Version v1.8.0

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US Patent Documents							
Note: Applicant is not required to submit a paper copy of cited US Patent Documents							
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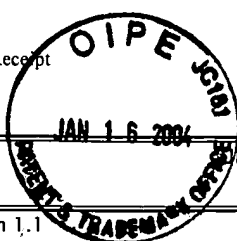
Remarks

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Examiner Name	Date



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Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney					

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Comments	

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of
InventionREGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A
PROCESSING CHAMBER

Application Number: 10/630640

10/630640

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

Search string: (5044871 or 5062770 or 5068040 or 5071485 or 5105556 or
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US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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	1	5044871	1991-09-03	Davis et al.			
	2	5062770	1991-11-05	Story et al.			
	3	5068040	1991-11-26	Jackson			
	4	5071485	1991-12-10	Matthews et al.			
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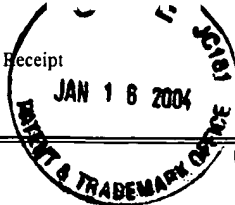
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Examiner Name

Date



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Stylesheet Version v1.1.1

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Date:	2003-07-29						
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	2	5306350	1994-04-26	Hoy et al.			
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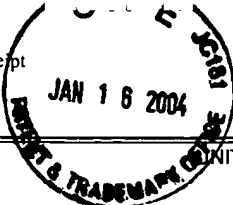
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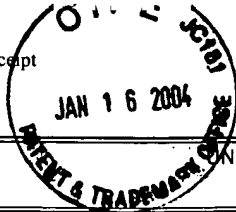
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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v1.8

Stylesheet Version v1.8.0

Title of
InventionREGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A
PROCESSING CHAMBER

Application Number: 10/630640 *10/630640*

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

Search string: (5904737 or 5908510 or 5928389 or 5932100 or 5934856 or 5934991 or 5944996 or 5955140 or 5965025 or 5976264 or 5979306 or 5980648 or 5981399 or 5989342 or 5992680 or 5994696 or 6001133 or 6005226 or 6017820 or 6024801 or 6029371 or 6035871 or 6037277 or 6053348 or 6056008 or 6063714 or 6067728 or 6077053 or 6077321 or 6082150 or 6085935 or 6097015 or 6099619 or 6100198 or 6110232 or 6114044 or 6128830 or 6140252 or 6145519 or 6149828 or 6159295 or 6164297 or 6171645 or 6186722 or 6200943 or 6203582 or 6216364 or 6224774 or 6228563 or 6228826).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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17	6001133	1999-12-14	DeYoung et al.
18	6005226	1999-12-21	Aschner et al.
19	6017820	2000-01-25	Ting et al.
20	6024801	2000-02-15	Wallace et al.
21	6029371	2000-02-29	Kamikawa et al.
22	6035871	2000-03-14	Eul-Yeol
23	6037277	2000-03-14	Masakara et al.
24	6053348	2000-04-25	Morch
25	6056008	2000-05-02	Adams et al.
26	6063714	2000-05-16	Smith et al.
27	6067728	2000-05-30	Farmer et al.
28	6077053	2000-06-20	Fujikawa et al.
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44	6186722	2001-02-13	Shirai	B1
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47	6216364	2001-04-17	Tanaka et al.	B1
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Remarks

Note: Remarks are not for responding to an office action.

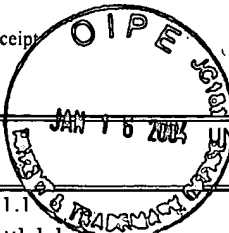
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The current electronic filing contains part 5 out of a total of 7 electronic filings.

Signature

Examiner Name

Date

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	UNITED STATES PATENT AND TRADEMARK OFFICE ACKNOWLEDGEMENT RECEIPT
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Electronic Version 1.1

Stylesheet Version v1.1.1

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Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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Stylesheet Version v18.0

Title of
Invention

REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A
PROCESSING CHAMBER

Application Number: 10/630640

10/630640

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

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US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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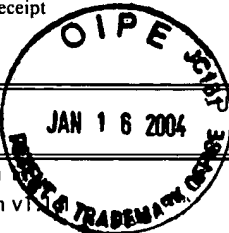
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The current electronic filing contains part 6 out of a total of 7 electronic filings.

Signature

Examiner Name

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	UNITED STATES PATENT AND TRADEMARK OFFICE ACKNOWLEDGEMENT RECEIPT
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Electronic Version
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Title of Invention	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER										
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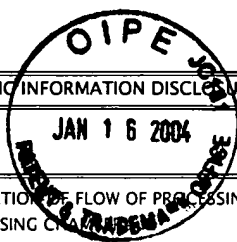
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Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
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<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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Submitted by:	Elec. Sign.	Sign. Capacity					
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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18
Stylesheet Version v18.0

Title of Invention	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAIN
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Application Number: 10/630640 *10/630640*

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

Search string: (5672204 or 5817178 or 6508259 or 20010019857 or 20010024247 or 20010041455 or 20010041458 or 20020001929 or 20020055323 or 20020074289 or 20020081533 or 20020088477 or 20020098680 or 20020106867 or 20020112740 or 20020112746 or 20020115022 or 20020117391 or 20020123229 or 20020127844 or 20020132192 or 20020141925 or 20020142595 or 20020150522 or 20030003762 or 20030008238 or 20030008518 or 20030013311 or 20030036023 or 20030047533).pn.

US Patent Documents

Note: Applicant Is not required to submit a paper copy of cited US Patent Documents

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	1	5672204	1997-09-30	Habuka			
	2	5817178	1998-10-06	Mita et al.			
	3	6508259	2003-01-21	Tseronis et al.	B1		

US Published Applications

Note: Applicant Is not required to submit a paper copy of cited US Published Applications

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21	20020150522	2002-10-17	Heim et al.	A1
22	20030003762	2003-01-02	Cotte et al.	A1
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Remarks

Note: Remarks are not for responding to an office action.

Non US Patent and Publication references shall be filed under a separate paper transmittal.

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